



2008 ISSCC Intel Paper Highlights

Justin Rattner
Chief Technology Officer
Intel Corporation



2008 ISSCC Intel Paper Summary

- **Under embargo until February, 3, 9 p.m. PST 2008**
- 14 new papers
- **Processor Technology:** First details of Silverthorne, the low-power IA processor and Tukwila, the new quad-core Itanium[®] processor - world's first 2 billion transistor microprocessor
- **Wireless Technology:** Four papers on new wireless developments including the first 65nm CMOS Class E power amp
- **Memory Technology:** Four papers including the world's first demonstrable multi-level cell (MLC) device using PCM technology
- **Tera-scale Technology:** Four papers including 2T gain cell DRAM built on 65nm CMOS technology with 2ns access time
- **Process Technology:** Re-publication of high-K metal gate CMOS technology paper from IEDM



Silverthorne: A Low Power 45nm IA Processor

Optimized for Mobile Internet Devices

"A Sub-1W to 2W Low-Power IA Processor for Mobile Internet Devices in 45nm High-K Metal-Gate CMOS"

- Ground-up new IA micro-architecture designed for low power operation
 - Dual issue in-order pipeline with HT
 - Fully Core 2 Duo ISA compatible
- 10x lower power than ULV Dothan
 - Deep power down (C6) architecture
 - Optimized register-file and cache 6T bit cells
 - CMOS mode on quad-pumped FSB IO
 - Split IO power supply



Sea-of-FUBs Chip Layout



Mobile Internet Devices

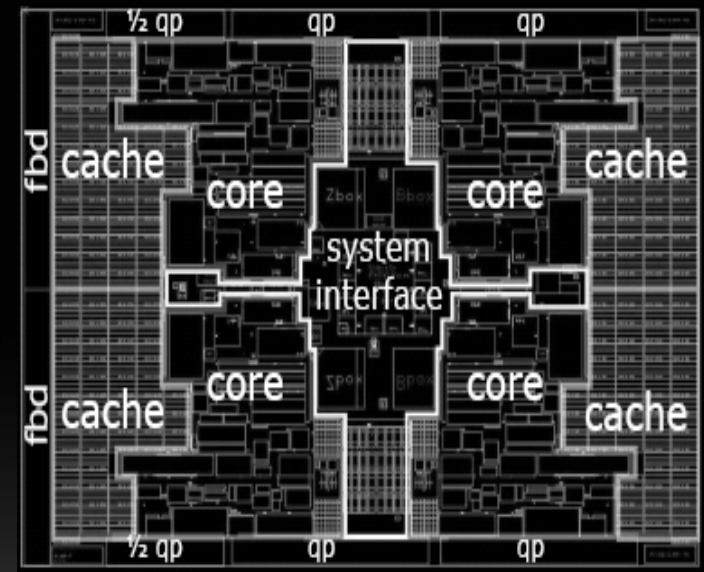
High Performance and Low Power Architecture Enables Full Internet Experience in Your Pocket

Tukwila: New Quad-Core Itanium® Processor

Worlds first 2 Billion Transistor Microprocessor

"A 65nm 2-Billion-Transistor Quad-Core Itanium® Processor"

- Upto 2GHz, Quad Core w/ Multi-Threading (8T)
- >2x* performance vs Dual-Core Itanium® Processor 9100 series
- 30MB on-die cache
- QuickPath interconnect and dual integrated memory controllers
- Advanced RAS
- Energy Efficiency



Tukwila Micrograph

**~2x performance at
25% more power (130W sku)**

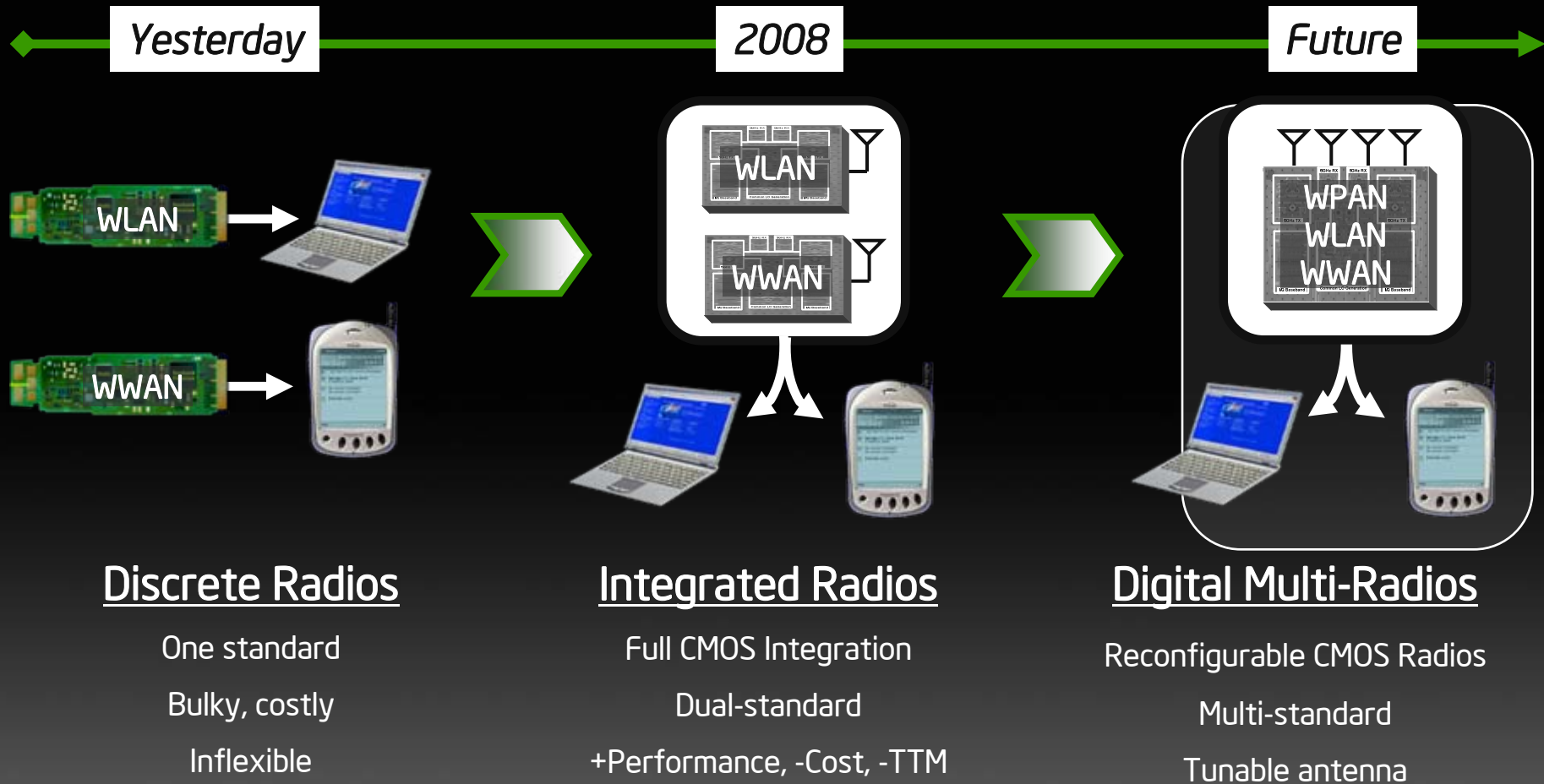
*>2x Performance → This is based on comparison between Intel's performance projections (1/15/08) on 4-socket benchmarks (TPC-C, SpecintRate, and SpecfpRate) for Tukwila Vs measurements on Intel Itanium® Processor 9100 Series (Montvale)

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The Wireless “Radio” Evolution



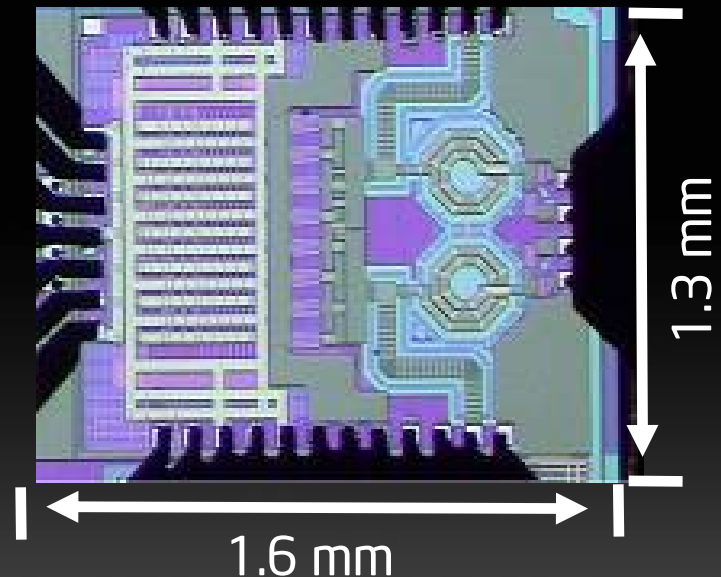
Vision: Connectivity Anytime, Anywhere for Everyone

65nm CMOS Power Amplifier for Multi-Radio

Worlds first Class E PA at 65nm

"A 28.6dBm, 65nm Class-E PA with Envelope Restoration by Pulse-Width and Pulse-Position Modulation"

- Delivers close to 1 Watt RF output power for WWAN
- Uses novel digital technique to introduce complex modulation required for high data rates
- Implemented in digital 65nm CMOS process for easy integration with other digital processing



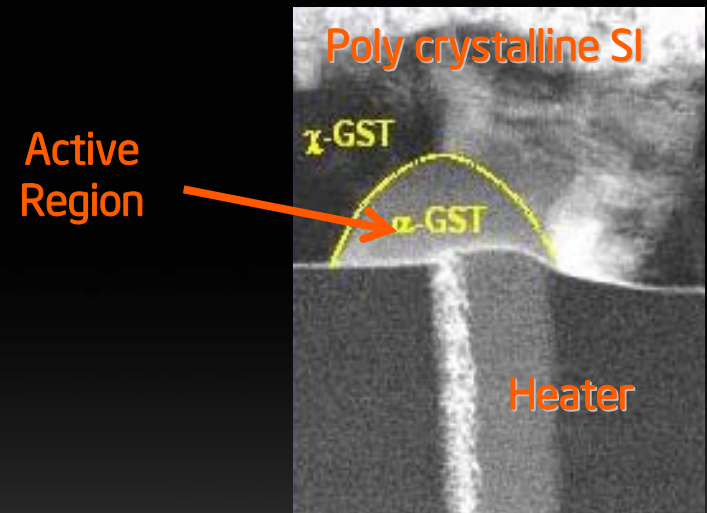
*First Class E PA in 65nm CMOS
(28.6dBm power output)*

Multi-Level Phase Change Memory*

First demonstrable MLC device using PCM technology

"A Multi-Level Cell Bipolar-Selected Phase Change Memory"

- 256 Mbit 90nm micro-trench technology
- A new "programming algorithm" creating two additional states between amorphous and crystalline
- Similar to observing H₂O in either a liquid (water) state or in a crystalline (ice) state.



World's first demonstrable multi-level cell (MLC) device using PCM technology

* Joint Development between Intel and ST Microelectronics

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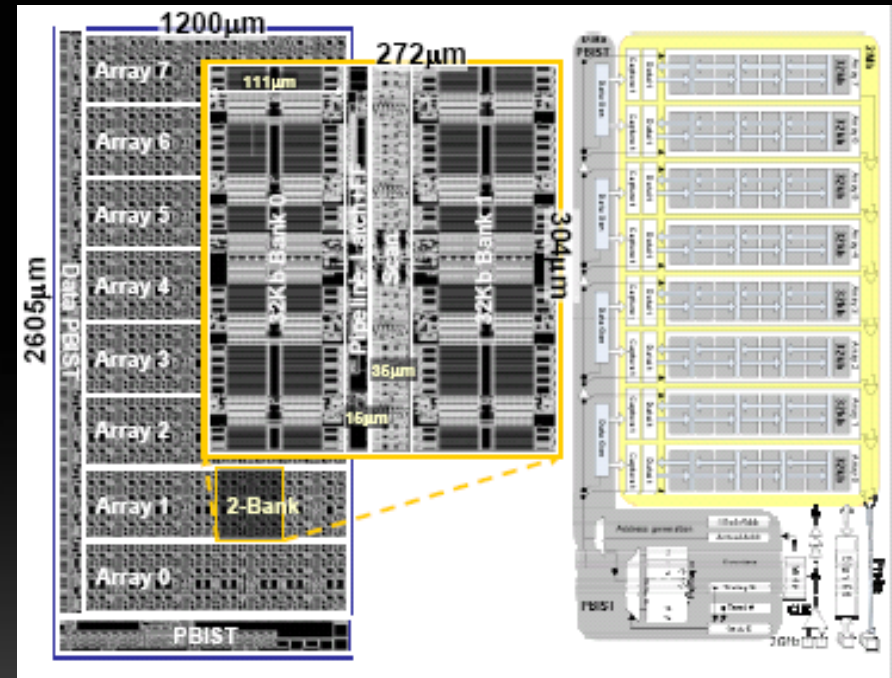


High-Density Integrated Memory

2T gain cell DRAM built on 65nm CMOS technology

"2GHz 2Mb 2T Gain-Cell Memory Macro with 128GB/s Bandwidth in a 65nm Logic Process"

- Twice the memory density vs. on-chip SRAM
- Much faster than DRAM: 128GB/s running at 2GHz
- 2ns access time
- Sustains 8-cycle successive access to the same memory bank



2Mbit macro with view of 2-bank and macro organization.

*Fast DRAM built on native
65nm CMOS Technology*

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- **Wireless Technology:** Four papers on new wireless developments including the first 65nm CMOS Class E power amp
- **Memory Technology:** Four papers including the world's first demonstrable multi-level cell (MLC) device using PCM technology
- **Tera-scale Technology:** Four papers including 2T gain cell DRAM built on 65nm CMOS technology with 2ns access time
- **Process Technology:** Re-publication of high-K metal gate CMOS technology paper from IEDM



List of Papers (15)

- **PROCESSOR**

- "A Sub-1W to 2W Low-Power IA Processor for Mobile Internet Devices in 45nm High-K Metal-Gate CMOS"
- "A 65nm 2-Billion-Transistor Quad-Core Itanium® Processor"

- **WIRELESS TECHNOLOGY**

- "A 1x2 MIMO Multi-Band CMOS transceiver with an integrated Front End in 90nm CMOS for 802.11 agn WLAN applications"
- "A 28.6dBm, 65nm Class-E PA with Envelope Restoration by Pulse-Width and Pulse-Position Modulation"
- "A 28mW Spectrum-Sensing Reconfigurable 20MHz 72dB-SNR 70dB-SNDR DT $\Delta\Sigma$ ADC for 802.11 n/WiMax Receivers"
- A 39.1-to-41.6GHz $\Sigma\Delta$ Fractional-N Frequency Synthesizer in 90nm CMOS

- **MEMORY TECHNOLOGY:**

- "A Multi-Level Cell Bipolar-Selected Phase Change Memory."
- "A 45nm Self-Aligned-Contact Process 1Gb NOR Flash with 5MB/s Program Speed."
- "A 50nm 8Gb NAND Flash Memory with 100MB/s Program Throughput and 200MB/s DDR Interface"

- **TERA-SCALE:**

- "A 27Gb/s Forwarded-Clock I/O Receiver using an injection-Locked LC-DCO in 45nm CMOS"
- "Energy-Efficient and Metastability-Immune Timing-Error Detection and Instruction-Replay-Based Recovery Circuits for Dynamic-Variation Tolerance"
- "A 320mV 56 μ W 411GOPS/W Ultra-Low Voltage Motion Estimation Accelerator in 65nm CMOS"
- "2GHz 2Mb 2T Gain-Cell Memory Macro with 128GB/s Bandwidth in a 65nm Logic Process"

- **45NM HIGH-K METAL GATE PROCESS TECHNOLOGY**

- "A 45nm Logic Technology with High-k+Metal Gate Transistors, Strained Silicon, 9 Cu Interconnect Layers, 193nm Dry Patterning, and 100% Pb-free¹ Packaging"
- "A 153Mb-SRAM Design with Dynamic Stability Enhancement and Leakage Reduction in 45nm High-K Metal-Gate CMOS Technology"

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Processor Technology Papers

"A 65nm 2-Billion-Transistor Quad-Core Itanium® Processor"

- World's first 2B+ Transistor Microprocessor → Enables a big leap in performance and capabilities e.g. quad-core, higher system integration, advanced RAS (Reliability, Availability, Serviceability, large cache (30MB) and QuickPath architecture → New high-speed QuickPath interconnect and dual QuickPath integrated memory controllers coupled with leading-edge RAS.
- Quad-core coupled with higher bandwidths and large caches enable doubling the performance of Tukwila over the current Intel® Itanium® 9100 series processor

"A Sub-1W to 2W Low-Power IA Processor for Mobile Internet Devices in 45nm High- K Metal-Gate CMOS"

- The 45nm high-k metal-gate silverthorne microarchitecture will implement ground-breaking power management techniques to aggressively reduce dynamic and leakage power.

*>2x Performance → This is based on comparison between Intel's performance projections (1/15/08) on 4-socket benchmarks (TPC-C, SpecintRate, and SpecfpRate) for Tukwila Vs measurements on Intel Itanium® Processor 9100 Series (Montvale)

3x Logic Circuits → This is based on doubling the cores and a new crossbar-based system interface (about the size of two cores)

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Wireless Technology Papers

"A 1x2 MIMO Multi-Band CMOS transceiver with an integrated Front End in 90nm CMOS for 802.11a/gn WLAN applications"

- Complete transceiver implemented in standard 90nm CMOS process for low power consumption, low cost and small form factors such as mobile internet devices, handheld or PDAs

"A 28mW Spectrum-Sensing Reconfigurable 20MHz 72dB-SNR 70dB-SNDR DT $\Delta\Sigma$ ADC for 802.11n/WiMax Receivers"

- **First reconfigurable ADC** proves increased process speed can be exploited for better performance; **Lowest power** consumption in its class; enables a radio to support WiFi/WiMAX bandwidths in a power efficient manner.

"A 39.1-to-41.6GHz $\Sigma\Delta$ Fractional-N Frequency Synthesizer in 90nm CMOS"

- **First mm-wave CMOS synthesizer** with <3kHz frequency resolution. Wirelessly transfer a full HD movie from one device to another in under one minute (compared to 1.5 hours for legacy WLAN)

"A 28.6dBm, 65nm Class-E PA with Envelope Restoration by Pulse-Width and Pulse-Position Modulation"

- First Class E power amplifier in 65nm CMOS

Memory Technology Papers

"A 153Mb-SRAM Design with Dynamic Stability Enhancement and Leakage Reduction in 45nm High-K Metal-Gate CMOS Technology"

- High-performance and low-power SRAM based on the industry's first 45nm high-k metal gate technology; provides a 2x density improvement, 10x leakage reduction, and 27 percent frequency increase over Intel's 65nm technology

"A 45nm Self-Aligned-Contact Process 1Gb NOR Flash with 5MB/s Program Speed."

- **Smallest reliable flash cell in 45nm** high-k metal gate technology
- 5 MB/sec program performance, the smallest periphery circuitry, and a robust sense scheme

"A 50nm 8Gb NAND Flash Memory with 100MB/s Program Throughput and 200MB/s DDR Interface"

- New high speed NAND flash technology that can greatly enhance access and transfer of data in devices using silicon for storage

"A Multi-Level Cell Bipolar-Selected Phase Change Memory"

- Provides for very fast read and writes at lower power than conventional flash; Allows for more stable data retention; Higher density at lower cost per Mbyte

Tera-scale Technology Papers

“Energy-Efficient and Metastability-Immune Timing-Error Detection and Instruction-Replay-Based Recovery Circuits for Dynamic-Variation Tolerance”

- A test chip with approximately 30% performance gain by “overclocking” the chip and up to 30% reduction in energy consumption by reducing voltage

“2GHz 2Mb 2T Gain-Cell Memory Macro with 128GB/s Bandwidth in a 65nm Logic Process”

- New category of integrated DRAM memory increasing performance of future tera-scale applications: Twice the memory density vs. on-chip SRAM, faster than DRAM: 128GB/s running at 2GHz

“A 320mV 56 μ W 411GOPS/W Ultra-Low Voltage Motion Estimation Accelerator in 65nm CMOS”

- Video motion-estimation accelerator could enable ultra-low power video encoding for mobile devices; 10x better throughput than best reported accelerator; ultra-low voltage of 0.3V yields

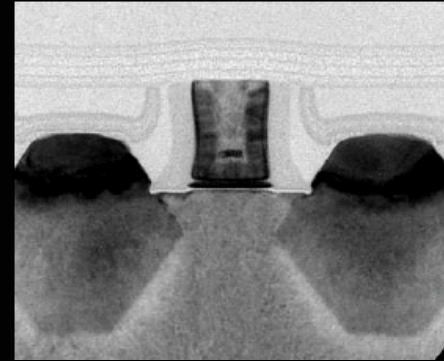
“A 27Gb/s Forwarded-Clock I/O Receiver using an injection-Locked LC-DCO in 45nm CMOS”

- The **best energy efficiency** of any I/O receiver over 20Gb/s: 1.6mW/Gb/s

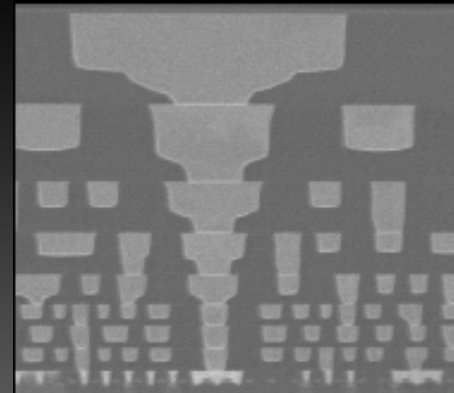
Process Technology 45nm Technology

"A 45nm Logic Technology with High-k+Metal Gate Transistors, Strained Silicon, 9 Cu Interconnect Layers, 193nm Dry Patterning, and 100% Pb-free¹ Packaging"

- The 'first' use of trench (rectangular) contacts to replace square contacts, for improved performance and local routing capability for improved layout density
- The technology features the smallest transistor pitch reported at the 45nm generation, providing better transistor packing density as well as a small static random access memory (SRAM) cell size of $0.346\mu\text{m}^2$.
- The process features nine copper interconnect layers with extensive use of low-k interlayer dielectrics for improved power and performance integrated with lead-free¹ packaging
- For the first time, the process integrates a very thick copper power redistribution interconnect layer using a polymer inter layer dielectric (ILD).



TEM micrograph of high-k + metal gate PMOS transistor



TEM Micrograph Cross-section of 8 of the 9 Cu interconnect layers